

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
M122-1943SERIAL NO.
10/071,456LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)APPLICANT
David L. Dickerson et al.FILING DATE
February 8, 2002GROUP
2814

U.S. PATENT DOCUMENTS

*Examining Division	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
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AM	AR	K. Ishimaru et al., Trench Isolation Technology with 1 Micron Depth n-and p-Wells for a Full CMOS SRAM Cell with a 0.4 Micron, . . . IEEE 1994 pps. 97-98					
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